

SEP 03 2004

Rahul Ganguli et al.

FILING DATE

August 22, 2003

GROUP ART UNIT

1752

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
JSR	4,833,051	05/23/89	Imamura	430	5	
	5,344,677	09/06/94	Hong	428	14	
	5,529,819	06/25/96	Camp, Jr.	428	14	
	5,814,381	09/29/98	Kuo	428	14	
JSR	6,099,792	08/08/00	Ganguli et al.	264	621	

US1

US2

US3

US4

US5

U.S. PATENT APPLICATION PUBLICATIONS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	US 2004/0028269 A1	02/12/04	Yamabe et al.	382	144	

US6

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
JSR	WO 01/59522 A1	08/16/01	PCT - Invalid				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

JSR	Kikugawa, S., Okada, K., Mishiho, H. and Sasuga, T., "Current Status of Hard Pellicle Development, <u>Asahi Glass Co., Ltd.</u> , December 10, 2001, pp 1-14
JSR	Laganza, Joseph, "157nm Reticle Handling Technology, <u>Sematech TDR</u> , December 12, 2001, pp 1-20

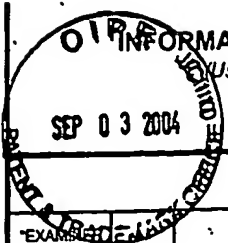
EXAMINER

John R. Gagliardi

DATE CONSIDERED

5/27/05

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INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
JSR	6,507,390	01/14/03	Ivaldi	355	75	
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JSR	6,593,034	07/15/03	Shirasaki	430	5	

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JSR		Cullins, Jerry, "LITJ360-157nm Mask Materials," International Sematech 157nm Technical Data Review, December 2001, pp 1-4
JSR		"Hard Pellicle Overview," International Sematech, February 4, 2002, pp 1-6

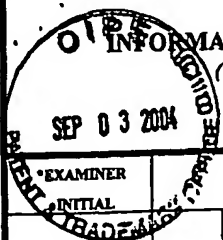
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Docket Number (Optional)

OSBE-101519

Application Number

10/646,356

Applicant(s)

Rahul Ganguli et al.

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

"157nm Blank Status," International Sematech, February 4, 2002, pp 1-3

Purging," International Sematech, February 4, 2002, pp 1-11

"157 nm Cleaning/Handling," International Sematech, February 4, 2002, pp 1-7

Ganguli, Rahul, et al., "Sol-gel fabrication of high quality photomask substrates," Proceedings of SPIE, Vol. 4889, October 1, 2002, pp 32-39

Meixner, D. Laurence, et al., "Porous silica frame for deep UV lithography," Proceedings of SPIE, Vol. 4889, October 3, 2002, pp 450-456

Bhattacharyya, Kaustuve, et al., "Investigation of reticle defect formation at DUV lithography," Photomask, February 2003, Vol. 19, Issue 2, 7 pages

Meixner, D. Laurence, "Porous silica frame for deep UV lithography," Proceedings of SPIE, Vol. 5040, February 25, 2003, pp 1018-1024

Jeng, De-Yin, et al., "Porous Silica Pellicle Frame," Proceedings of SPIE, Vol. 5256, September 9, 2003, pp 213-221

EXAMINER

John Ruggles

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5/27/05

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